

*“Modeling of chemical processes in the low pressure capacitive radio frequency discharges in a mixture of Ar/C<sub>2</sub>H<sub>2</sub>”*. Ariskin DA, Schweigert IV, Alexandrov AL, Bogaerts A, Peeters FM, Journal of applied physics **105**, 063305 (2009). <http://doi.org/10.1063/1.3095760>